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(71) Applicant (for all designated States except US): **MI-CRON TECHNOLOGY, INC.** [US/US]; 8000 South Federal Way, Boise, ID 83716 (US).

(72) Inventor; and

(75) Inventor/Applicant (for US only): **PLUM, Todd, Jack-son** [US/US]; 5449 S. Alyssum Place, Boise, ID 83716 (US).

(74) Agent: **MATKIN, Mark, S.**; Wells St. John P.S., 601 W. First Ave., Suite 1300, Spokane, WA 99201 (US).

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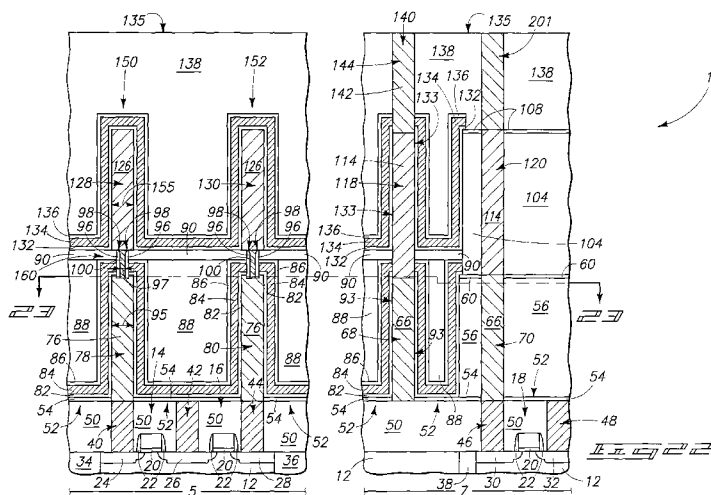
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(57) Abstract: Some embodiments include methods of forming capacitors. A first section of a capacitor may be formed to include a first storage node, a first dielectric material, and a first plate material. A second section of the capacitor may be formed to include a second storage node, a second dielectric material, and a second plate material. The first and second sections may be formed over a memory array region, and the first and second plate materials may be electrically connected to first and second interconnects, respectively, that extend to over a region peripheral to the memory array region. The first and second interconnects may be electrically connected to one another to couple the first and second plate materials to one another. Some embodiments include capacitor structures, and some embodiments include methods of forming DRAM arrays.